

Veeco GEN II

Oxide Molecular Beam Epitaxy

Location: Science and Engineering South, 109B



Description

The Applied Epi (now Veeco) GEN II MBE is a single-wafer molecular beam epitaxy system, used to grow high purity metal oxide films. The growth chamber is held at ultra-high vacuum and the metal oxide films are grown at a slow deposition rate, which allows them to grow epitaxially. The instrument has up to 6 effusion cells for metals and also an oxygen source. It was acquired, used, in 2004.

Robert Klie's Interface Physics Group currently operate this instrument. They are using it to grow Manganese oxide and Lithium Oxide films.